



AB1752  
FF6/k,  
5/28/99  
PJ

**IN THE UNITED STATES PATENT AND TRADEMARK OFFICE**

Inventor: KAICHIRO NAKANO, et al.

Serial No.: 09/036,219

Filed: March 6, 1998

Title: CHEMICALLY AMPLIFIED RESIST LARGE IN TRANSPARENCY AND SENSITIVITY TO EXPOSURE LIGHT LESS THAN 248 NANOMETER WAVELENGTH AND PROCESS OF FORMING MASK

Examiner: J. CHU

Group Art Unit: 1752

May 21, 1999

Box Non-Fee Amendment  
Assistant Commissioner for Patents  
Washington, D. C. 20231

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MAY 27 1999

GROUP 170

**AMENDMENT**

SIR:

Responsive to the Office Action dated April 27, 1999, please amend the application as follows:

**IN THE CLAIMS:**

Please cancel claims 2, 4, 7 and 8 without prejudice.

**REMARKS**

In the outstanding Office Action restriction has been issued to elect the claims between claims 1-8, drawn to resist composition, classified in claim 430, subclass 270.1 and claims 9-20, drawn to process of use, classified in class 430, subclass 325.

In addition an election requirement to elect a single species has been issued by the Examiner.

Any fee due with this paper, not fully covered by an enclosed check, may be charged on Deposit Acct. No. 08-1634

Filed by Express Mail  
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on 5-21-99  
pursuant to 37 C.F.R.1.10.  
by Francis Doyle